

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Ichiro OKABE *et al.*

Title: METHOD OF FORMING A FINE PATTERN, AND METHOD OF  
MANUFACTURING A SEMICONDUCTOR DEVICE, AND A  
SEMICONDUCTOR DEVICE HAVING A FINE PATTERN

Appl. No.: 09/597,161 ✓

Filing Date: 6/20/2000 ✓

Examiner: J. Diaz

Art Unit: 2815 ✓

RECEIVED  
APR - 3 2002  
TECHNOLOGY CENTER 2800

PROPOSED CHANGES TO THE DRAWINGS

Commissioner for Patents  
Washington, D.C. 20231

Sir:

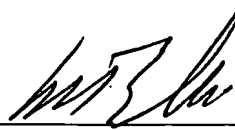
Applicants propose amending Figs. 1C, and 4C as shown in red on the attached  
copies. With the Examiner's approval, changes will be made to the formal drawings in due  
course.

Respectfully submitted,

Date

3/29/02

By



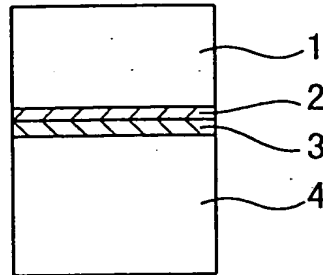
FOLEY & LARDNER  
3000 K. Street, N.W.  
Suite 500  
Washington, D.C.

Telephone: (202) 672-5485  
Facsimile: (202) 672-5399

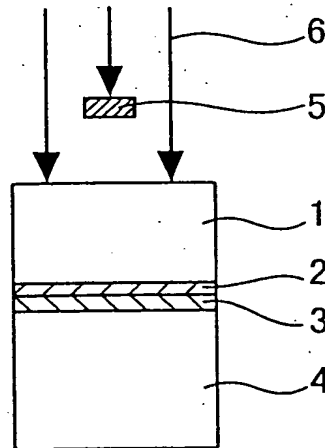
William T. Ellis  
Attorney for Applicant  
Registration No. 26,874

approved by Examiner  
J  
6/7/02

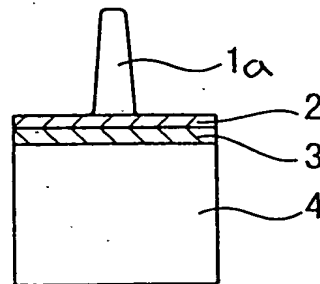
*FIG. 1A*



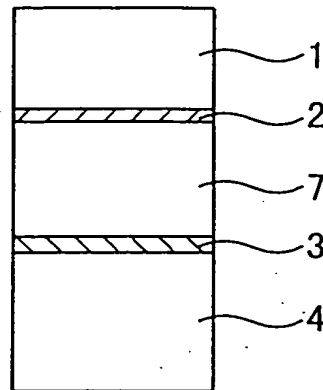
*FIG. 1B*



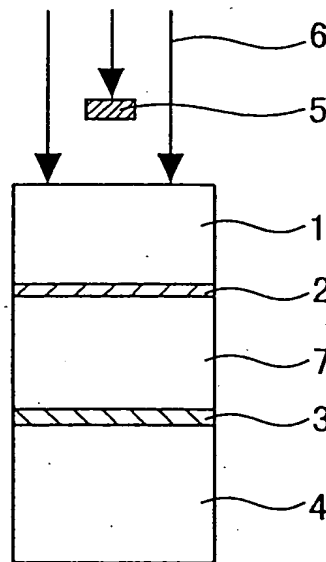
*FIG. 1C*



**FIG. 4A**



**FIG. 4B**



**FIG. 4C**

